

## AMENDMENT OF SPECIFICATION

[0007] ~~An object of the present~~Embodiments of the invention is to provide a plasma processing apparatus adapted to uniform the plasma density within a chamber for generating the plasma, without necessitating a specific chamber having a specific shape.

[0008] ~~The~~A plasma processing apparatus according to the present invention comprises: a chamber having ~~defining~~ at least one opening and for generating constructed for retaining a plasma; a dielectric member ~~provided to air-tightly cover~~ positioned to sealingly cover the at least one opening; at least one wave guide provided ~~in the exteriorly~~ of the chamber such that its one end side thereof opposes the dielectric member; an electromagnetic wave source ~~provided on the other end side of~~ operatively coupled to the at least one wave guide; a plurality of holes defined by a side of the at least one wave guide that is in opposition to ~~provided on a surface opposing the dielectric member of the wave guide~~; and hole area adjusting means including a reciprocable plate portion provided in at least one, but not all, of the holes so as to adjust the opening area of the at least one hole, and thereby modulate the waveform of a propagating wave during operation thereof.